

## Abstract of the Disclosure

The invention relates to a large-apertured microlithography projection lens. The diaphragm error is also systematically corrected, so that the pupil plane is slightly curved and the lens can be stopped down without comprising quality. The system diaphragm of the projection lens is located in the area of the last lens cluster of positive refractive power on the image side. The telecentrics of the projection lens remain stable on the image side during stopping down.

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